Notice of Allowability	Application No.	Applicant(s)	
	09/753,664	TSAU, LIMING	
	Examiner	Art Unit	
	Khiem D Nguyen	2823	
The MAILING DATE of this communication appeall claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED or other appropriate com IGHTS. This application in	D in this application. If not included imunication will be mailed in due c	d ourse. THIS
 This communication is responsive to <u>08-28-2003</u>. The allowed claim(s) is/are <u>1-14</u>. The drawings filed on <u>21 September 2001</u> are accepted by the drawings filed on <u>21 September 2001</u> are accepted by the drawings filed on a claim for foreign priority unit at a claim	der 35 U.S.C. § 119(a)-(d e been received. e been received in Applica	ation No	on from the
International Bureau (PCT Rule 17.2(a)). * Certified copies not received: 5. Acknowledgment is made of a claim for domestic priority uses a claim for dome	ınder 35 U.S.C. § 119(e) (application has been recei	to a provisional application). ved.	on from the
Applicant has THREE MONTHS FROM THE "MAILING DATE" of below. Failure to timely comply will result in ABANDONMENT of 7. A SUBSTITUTE OATH OR DECLARATION must be subtined in the subtine subt	this application. THIS To	HREE-MONTH PERIOD IS NOT E	XTENDABLE
 8. CORRECTED DRAWINGS must be submitted. (a) including changes required by the Notice of Draftsper 1) hereto or 2) to Paper No (b) including changes required by the proposed drawing (c) including changes required by the attached Examiner Identifying indicia such as the application number (see 37 CFR 1 each sheet. 	correction filed, was a constant.	which has been approved by the Ex at or in the Office action of Paper N	lo
9. DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT FOR 1	Sit of BIOLOGICAL MATTHE DEPOSIT OF BIOLO	ATERIAL must be submitted. No GICAL MATERIAL.	ote the
Attachment(s)			
 1☐ Notice of References Cited (PTO-892) 3☑ Notice of Draftperson's Patent Drawing Review (PTO-948) 5☐ Information Disclosure Statements (PTO-1449), Paper No 7☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material 	4☐ Interv 6☐ Exam	e of Informal Patent Application (Priew Summary (PTO-413), Paper National Patent/Comment Statement of Reasons for A	No

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DETAILED ACTION

Allowable Subject Matter

Claims 1-14 are allowed.

Reasons For Allowance

The following is a statement of reasons for the indication of allowable subject matter: The prior art taken alone or in combination neither discloses nor makes obvious the instant process of claims as a whole. Specifically, the prior art of record, Ma et al. (U.S. Patent 6,329,234) discloses a metal-insulator-metal (MIM) capacitor process, comprising: forming a first dielectric layer (FIG. 8, 12) on the substrate (FIG. 8, 10); forming a first metal layer (FIG. 8, 16) in the first dielectric layer, forming an etch stop layer (FIG. 8, 20) on the first dielectric layer; forming a second dielectric layer (FIG. 4, 30) on the stop layer; forming a first patterned mask layer (FIG. 4, 40) on the second dielectric layer; and performing an etching process, using the first patterned mask layer as an etching mask, so that a first opening (FIG. 8, 80, 82) and a second opening (FIG. 8, 42) are formed in the second dielectric layer; and forming a second metal layer (FIG. 9, 90) over the substrate so as to fill the first and second openings (col. 7, line 41 to col. 8, line 62) but fails to disclose or suggest Applicant's steps of forming a second patterned mask layer on the second dielectric layer and a part of the stop layer; performing a further etching process, using the second patterned mask layer as a further etching mask, to etch the stop layer below the second opening and to partially etch a third opening adjacent the second opening in the second dielectric layer without exposing the stop layer thereunder, as recited in the pending independent claims.

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Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Khiem D Nguyen whose telephone number is (703) 306-0210. The examiner can normally be reached on Monday-Friday (8:00 AM - 5:00 PM).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Olik Chaudhuri can be reached on (703) 306-2794. The fax phone numbers for the organization where this application or proceeding is assigned are (703) 746-9179 for regular communications and (703) 746-9179 for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-0956.

K.N.

September 15, 2003

Mr Millian